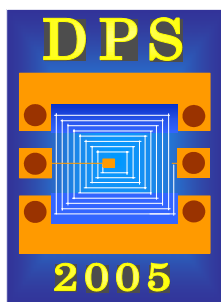


FIRST ANNOUNCEMENT AND CALL FOR PAPERS
27th International Symposium on Dry Process
(DPS 2005)



November 28-30, 2005
Ramada Plaza Jeju Hotel, Jeju, Korea

Sponsored by The Institute of Electrical Engineers of Japan

Co-Sponsored by The Japan Society of Applied Physics

In conjunction with The Institute of Electronics, Information and Communication Engineers

The Electrochemical Society of Japan, Electrochemical Society Japan Chapter

The 21st Century COE "Plasma-Nano" (Nagoya Univ., Japan), The Korean Vacuum Society

The Korean Physical Society, The Korean Electronic Engineering Society

Center for Advanced Plasma Surface Technology (Sungkyunkwan Univ., Korea)

Dry processes are the state of the art technologies leading the way through ultra-high performance in microelectronic devices. The DPS provides for 26 years a valuable forum of discussions on science and technology of new developments in this field. Present 27th symposium is for the first time jointly organized with Korean colleagues in Jeju and a special issue of Thin Solid Films will be published besides the Extended Abstracts. The DPS Organizing Committee invites you to the conference and welcomes the submission of your papers.

General Topics and Arranged Sessions

Theme: Dry processes and related technologies from fundamentals to applications

Topics: Mechanisms of plasma-induced surface reactions / Diagnostics and monitoring of plasmas and reaction surfaces / Damages induced by photon-, electron-, and ion-irradiation onto surface / Process technologies for etching, CVD and surface treatment / Dry process for low-k, high-k, and new materials / MEMS technologies / Process technologies for flat panel display (LCD, PDP, Organic ELD) / Nano technologies and bio-applications / Environmental technologies / Equipment technology for dry processes / New dry process concept (microplasmas, atmospheric plasmas, etc)

Arranged Sessions:

(1) Flat panel display (LCD, PDP, Organic EL, FED), (2) Low-k material processing (etch, CVD, integration)

Submission of Extended Abstracts

Two page (A4) *camera-ready* abstract, including figures and references, should be submitted by e-mail to the conference secretariat (dps2005@plasma.coe.nagoya-u.ac.jp) by **July 20, 2005**. The abstract template can be downloaded from <http://www.plasma.coe.nagoya-u.ac.jp/DPS2005/>. After the reviewing process, authors will be notified of acceptance or rejection of their abstracts by *September 15, 2005*. Based on scientific quality, the DPS Organizing Committee will select about 20 oral presentations. Accepted contributions and invited papers will appear on the DPS 2005 Extended Abstract.

Special Issue of "Thin Solid Films"

Participants willing to have their papers (invited, oral and/or poster presentations) included in the special issue should hand in the manuscripts at the registration desk on the first day of the symposium. All manuscripts will be reviewed and based on their scientific quality the accepted papers will be published in a special issue of "Thin Solid Films" (Elsevier Science).

Invited Speakers

Fundamentals: J.P. Booth (Ecole Polytechnique), M. Kushner (Univ. Illinois), E. Stamate (Nagoya Univ.)

Diagnostics: G. Cunge (CNRS), L. J. Overzet (Univ. Texas at Dallas), R. McWilliams (Univ. California at Irvine)

Plasma Damages: P. Aum (Spider Systems), **Process technologies:** U-In. Chung (Samsung), S-K. Lee (Hynix),

S. Sinnott (Univ. of Florida) **Nanotechnology:** J.-M. Ting (National Cheng Kung Univ.), Y. Baba (Nagoya Univ.)

New dry process concept: A. Schwabedissen (JE PlasmaConsult) **Low-k, high-k:** K. Komura (MIRAI), H.

Hayashi (Toshiba Corp.), K. Yonekura (Renesas), K-K. Choi (Magnachip Com.), W. J. Yoo (National Univ. of Singapore), **FPD processes:** J. Jan (Kyunhee Univ.), J. Kim (Samsung), Ki-W. Whang (Seoul National Univ.), H. Kobayashi (ALTEDEC), A. Howling (Ecole Polytechnique Federale de Lausanne); [Titles were included in the web site]

Registration Fee

The registration fee covers the Conference Abstracts, banquet ticket and coffee breaks:

Early registration (before September 30, 2005): 38,000 JPY for general and 17,000 JPY for student.

Late registration (after October 1, 2005): 44,000 JPY for general and 17,000 JPY for student.

Secretariat –DPS 2005

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